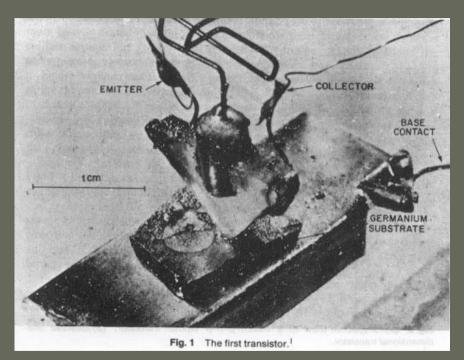
# Moving Towards Integrated Circuits

History and Fabrication

## Transistor History

- First transistors were hybrid devices made from germanium and operated in a vacuum tube (1947).
- The first transistor radio (by Regency Division of IDEA) was made from 4 transistors and required a 22.5 V battery (1954).
- The bipolar junction transistor was developed in the late 1950s (still hybrid).
- The movement to monolithic devices came in the 1960s with the dawn of silicon microfabrication.
- BJTs were the earliest transistors and are current-controlled devices. They can carry larger currents and perform well at high frequencies.
- MOSFETs are voltage controlled devices. They are symmetrical, can operate at low power, can be made smaller, and have near infinite input resistance.

#### **Transistors**

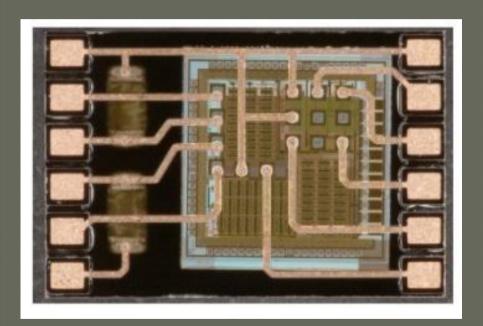


Bell Labs Engineers: Shockley, Brattain and Bardeen invented the point-contact transistor in 1947 and the hybrid BJT in 1948

Transistors were originally manufactured from Germanium.

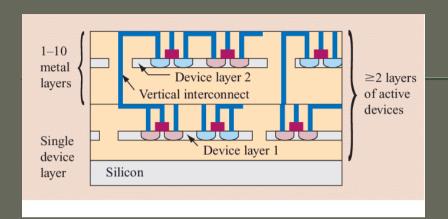
Silicon became the material of the future because of it's high operating temperature, inert material qualities, and cost.

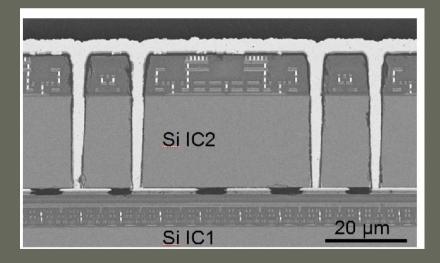
#### **Transistors**



Silicon fabrication processes allowed for smaller feature sizes and increased density of transistors per unit area.

Transistor are small, but contact pads, resistors and capacitors take up a lot of space.





#### **Transistors**

Just like in cities, when we run out of space, we go vertical!

#### Semiconductor Fabrication

 Fabrication is done in a largely automated process to reduce manufacturing issues related to humans coming in and out of the plant.



#### General Process



Photoresist

Coat of Photoresist A photosensitive resin, photoresist is coated.

Part to be processed



Cross Section of Silicon Wafer





Etching

The part with the photoresist pattern formed by the development as a protective film is not etched, and the part without photoresist is etched.

Process 6

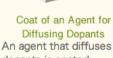
Development In the same way as a photograph is developed, the process of development forms photoresist patterns of the exposed design drawing.



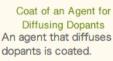
Exposure A photomask (design drawing) is transcribed onto the photoresist in the similar way as a photograph is printed onto photographic paper.

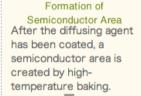


Removal of Photoresist After processing, used photoresist is removed.



Diffusion -Source









Completion of an Integrated Circuit on the Wafer Integrated circuits cover the wafer processed by microprocess technology.



Formation of Integrated Circuits By repeating these processes, a variety of different types of circuits and then integrated circuits are made.



Formation of Wiring Processing including photoresist coating, exposure, development, and etching is carried out and form wiring which is made of aluminum or copper.



Dicing a Wafer The wafer is diced into chips.



IC Chip Each piece of the diced wafer is an IC chip.



Completion of LSI

### General Process

## Health and Environmental Impacts of Manufacturing

- Many chemicals associated with semiconductor fabrication are toxic to humans and to the environment.
- Water usage is a huge factor as well.
- A typical facility uses 240,000 kW-hrs of electricity and over 2 million gallons of water every day. (The average person uses about 100 gallons of water a day).
- Chemicals require disposal mechanisms to protect the water table.
- Not to mention issues with disposal of actual circuits after their useful life ends (arsenic, gallium and heavy metals leach out in the environment)